

ABSTRACT

PHOTOSENSITIVE RESIN COMPOSITION, PHOTOSENSITIVE ELEMENT
USING THIS, METHOD OF MANUFACTURING RESIST PATTERN, RESIST
5 PATTERN, AND RESIST PATTERN LAMINATED SUBSTRATE

Disclosed are a photosensitive resin composition
comprising a photosensitive resin (A), a photopolymerization
initiator (B), and a flame retardant (C), in which a content
10 of halogen atoms or antimony atoms in the flame retardant is
5% or less by weight; a photosensitive element using this; a
method of manufacturing a resist pattern; a resist pattern;
and a resist pattern laminated substrate.



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